IN THE CLAIMS:

Please AMEND claim 16, 18 and 20, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-15. (Cancelled)

16. (Currently Amended) An anti-vibration apparatus comprising:

a table;

a pneumatic spring for applying a force to said table;

an electromagnetic actuator for applying a force to said table; and

a first generator which generates a driving signal for said electromagnetic actuator based on at least one of a target position and a target speed with respect to a movable object on of a movable object which is supported by said table and movable relative to said table.

- 17. (Previously Presented) An apparatus according to claim 16, further comprising a second generator which generates a signal for changing a pressure in said pneumatic spring based on at least one of the target position and the target speed.
- 18. (Currently Amended) An apparatus according to claim 16, wherein said first generator includes a filter which filters a signal with respect corresponding to at least one of the target position and the target speed.

- 19. (Previously Presented) An apparatus according to claim 18, wherein a cutoff frequency of said filter has a value within a controllable frequency range of said pneumatic spring.
- 20. (Currently Amended) An apparatus according to claim 17, wherein said second generator includes a filter which filters a signal with respect corresponding to at least one of the target position and the target speed.
- 21. (Previously Presented) An apparatus according to claim 20, wherein a cutoff frequency of said filter has a value within a controllable frequency range of said pneumatic spring.
- 22. (Previously Presented) An exposure apparatus for exposing a substrate to a pattern, said apparatus comprising an anti-vibration apparatus defined in claim 16.
- 23. (Previously Presented) An apparatus according to claim 22, further comprising a movable stage as the movable object.
- 24. (Previously Presented) A device manufacturing method comprising:

 a step of exposing a substrate to a pattern using an anti-vibration apparatus defined in claim 16.

25. (Previously Presented) A device manufacturing method comprising:

a step of exposing a substrate to a pattern using an exposure apparatus defined in claim 22.